



INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) XA-9335		Application Number 09/615,081		
				Applicant(s) Yutaka SUENAGA et al.				
				Filing Date July 12, 2000		Group Art Unit 2872		
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
J.T.	AA	5,737,137	04/07/98	Cohen et al.	359	859		
J.T.	AB	4,812,028	03/14/89	Matsumoto	350	444		
J.T.	AC	4,293,186	10/06/81	Offner	350	27		
J.T.	AD	5,734,496	03/31/98	Beach	359	362		
J.T.	AE	5,717,518	02/10/98	Shafer et al.	359	357		
J.T.	AF	5,742,436	04/21/98	Furter	359	727		
	AG							
	AH							
	AI							
	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
J.T.	AL	WO 95/32446	11/30/95	WIPO	—	—	Abstract	
J.T.	AM	0 779 528	06/18/97	EPO	—	—		
	AN							
	AO							
	AP							
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
J.T.	✓	Owen, G. et al., "A Catadioptric Reduction Camera for Deep UV Microlithography", <u>Microelectronic Engineering</u> , Vol. 11, No. 1/04, April 1, 1990, pages 219-222.						
J.T.	✓	Haga, T. et al., "Large-Field (> 20 x 25mm ²) Replication by EUV Lithography", <u>Microelectronic Engineering</u> , Vol. 30, No. 1, 1996, pages 179-182						
EXAMINER 				DATE CONSIDERED 04/13/01				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								